

STD LSNitride2 12/14/2018	NEW RECIPE
Date	12/14/18
Standard LS Nitride2 Coat	
Coat time, min	10
Standard LS Nitride2 Deposition	
Deposition time, min	30
LF power setup, W	90
RF power setup, W	30
LF time, sec	2.25
HF time, sec	6
Pressure, mTorr	800
Gass flow, sccm	
2%SiH	520
NH3	18
N2	980
T, C	~300
Thickness, nm	222.28
Dep.rate, nm/min	7.41
Index at 632.8nm	1.969
Index at 1550nm	1.933
Stress, MPa	-24.86
BHF, nm/min	24.31
Std. clean, min	40

Recipe Name: STD LSNitride2 12/14/18
 Category: Production

Steps:

- Initial
- Pressure Stab
- HF Process Step**
- LF Process Step
- Loop for 30:00
- End

Step Name: HF Process Step

Step Termination: End By Fixed Time, Time 0 6.0 min : s

Pressure: 800.0 mTorr

Gas (sccm):

SiH4	520	sccm
NH3	18.0	sccm
N2	980	sccm
N2O	0	sccm
CF4, O2	0	sccm

RF: Setpoint 30 W, AMN Mode Automatic, Load/Tune 50.0 50.0 %, LF Setpoint 0 W

Recipe Name: STD LSNitride2 12/14/18
 Category: Production

Steps:

- Initial
- Pressure Stab
- HF Process Step
- LF Process Step**
- Loop for 30:00
- End

Step Name: LF Process Step

Step Termination: End By Fixed Time, Time 0 2.3 min : s

Pressure: 800.0 mTorr

Gas (sccm):

SiH4	520	sccm
NH3	18.0	sccm
N2	980	sccm
N2O	0	sccm
CF4, O2	0	sccm

RF: Setpoint 0 W, AMN Mode Automatic, Load/Tune 50.0 50.0 %, LF Setpoint 50 W